



PATENT Customer No. 22,852 Attorney Docket No. 04329.2409

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re A	Application of:	)
Kei YOSHIKAWA et al.		) Group Art Unit: 2623
Application No.: 09/662,219  Filed: September 14, 2000		Examiner: S. Ahmed RECEIVED
For:	PATTERN CORRECTING METHOD OF MASK FOR MANUFACTURING A SEMICONDUCTOR DEVICE AND RECORDING MEDIUM HAVING RECORDED ITS PATTERN CORRECTING METHOD	) NOV 1°0 2003 ) Technology Center 2600 ) ) ) ) )
P.O. E	nissioner for Patents Box 1450 ndria, VA 22313-1450	

## <u>AMENDMENT</u>

In response to the Office Action dated July 14, 2003, the period for response having been extended to November 14, 2003, by a request for extension of one month and fee payment filed concurrently herewith, please reexamine and reconsider the application in view of the amendments and appended remarks.

Amendments to the Specification are included in this paper.

Amendments to the Claims are reflected in the listing of claims in this paper.

Remarks/Arguments follow the amendment sections of this paper.

Astachments to this amendment include a new Abstract.

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